

“Numerical investigation of HBr/He transformer coupled plasmas used for silicon etching”.
Gul B, Tinck S, De Schepper P, Aman-ur-Rehman, Bogaerts A, Journal of physics: D:
applied physics **48**, 025202 (2015). <http://doi.org/10.1088/0022-3727/48/2/025202>